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(54) **TARGET PROFILE FOR A PHYSICAL VAPOR DEPOSITION CHAMBER TARGET**

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(**) Term: **15 Years**

(21) Appl. No.: **29/690,617**

(57) **CLAIM**

(22) Filed: **May 9, 2019**

We claim the ornamental design for a target profile for a physical vapor deposition chamber target, as shown and described.

Related U.S. Application Data

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(51) **LOC (12) Cl.** **13-03**

(52) **U.S. Cl.**

USPC **D13/184**

(58) **Field of Classification Search**

USPC D13/182; D15/144.1, 144.2, 199

CPC H01L 21/67742; H01L 21/0226; H01L

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2224/75186; H01L 2224/761185; H01L

2224/76186; H01L 2221/68363

See application file for complete search history.

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DESCRIPTION

FIG. 1 is a top perspective view of a target profile for a physical vapor deposition chamber target, according to the new design.

FIG. 2 is a bottom perspective view thereof.

FIG. 3 is a top plan view thereof.

FIG. 4 is a bottom plan view thereof.

FIG. 5 is a right side elevation view thereof.

FIG. 6 is a left side elevation view thereof.

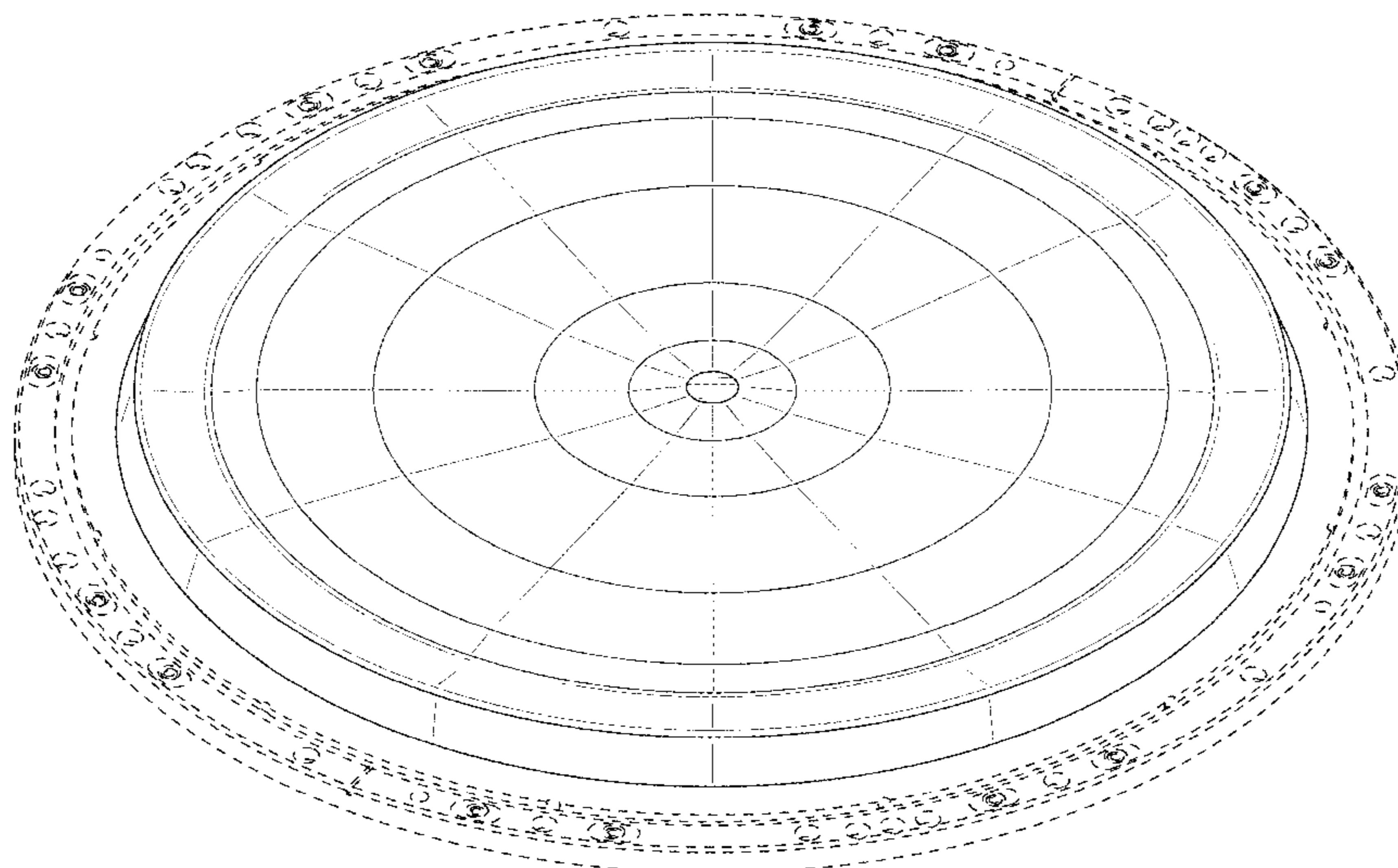
FIG. 7 is a front elevation view thereof.

FIG. 8 is a back elevation view thereof; and,

FIG. 9 is an enlarged cross sectional view taken along line 9-9 in FIG. 4.

Dashed lines in FIGS. 1-9 represent features of the target profile for a physical vapor deposition chamber target that form no part of the claimed design.

1 Claim, 7 Drawing Sheets



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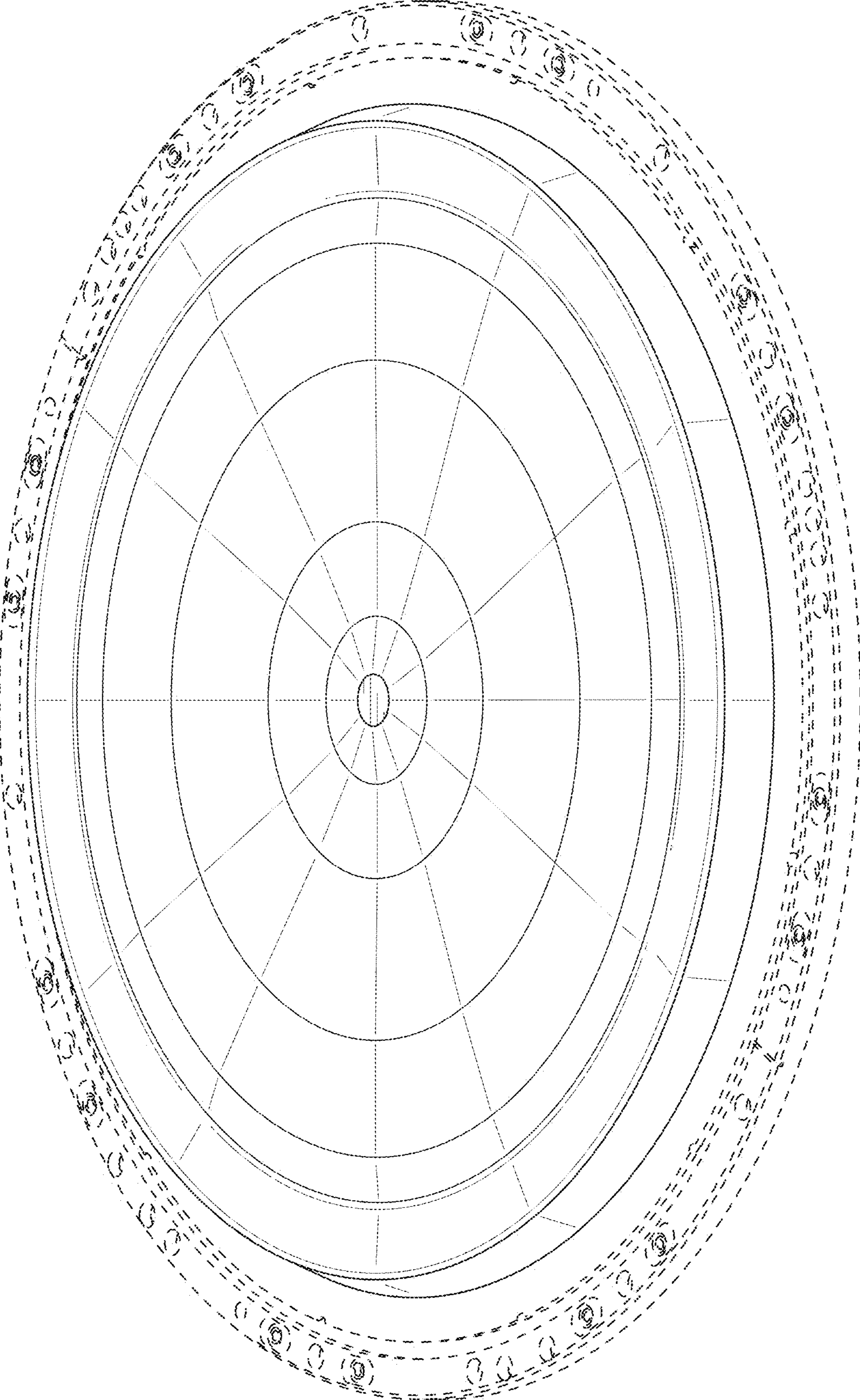


FIG. 1

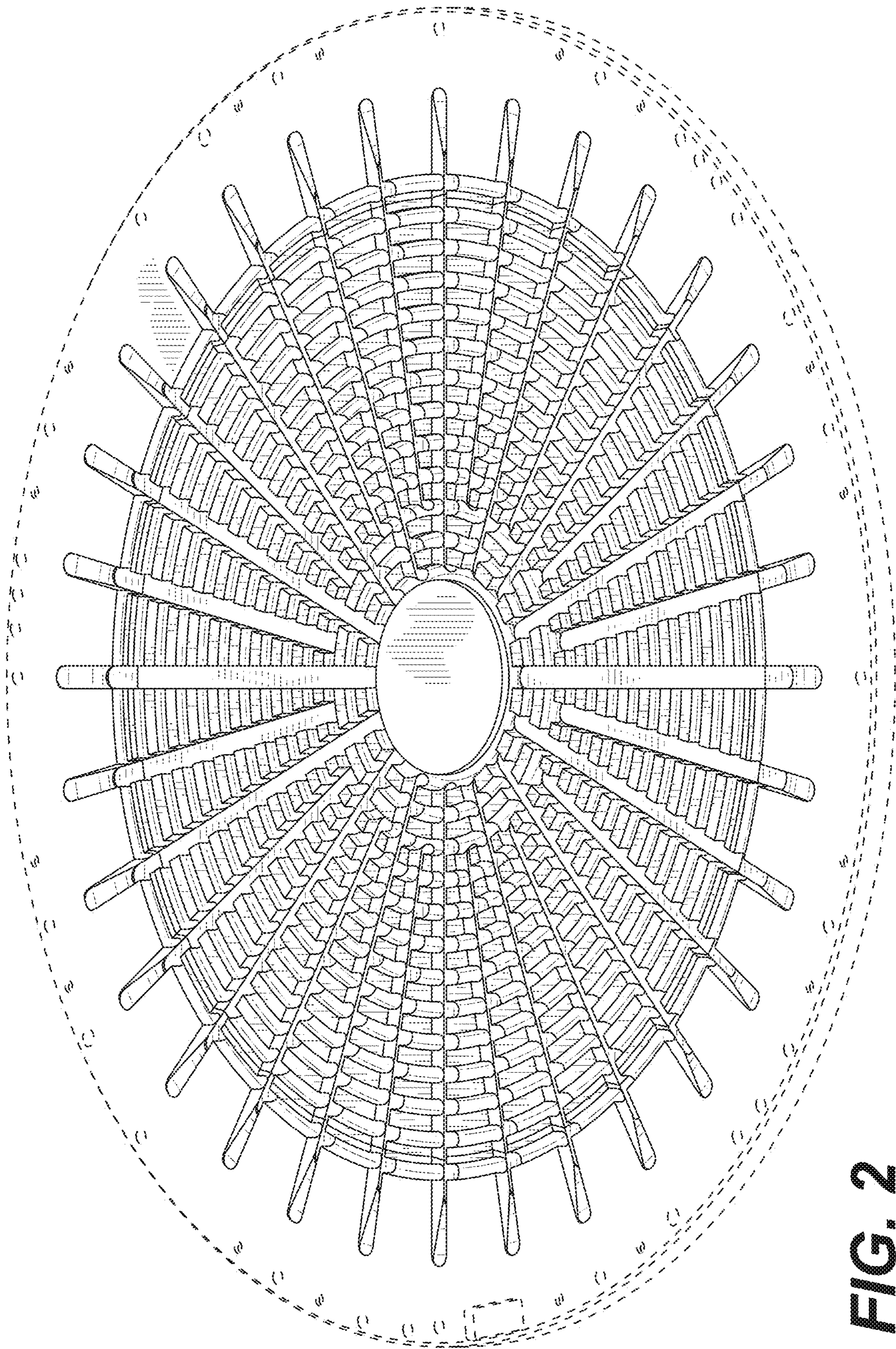


FIG. 2

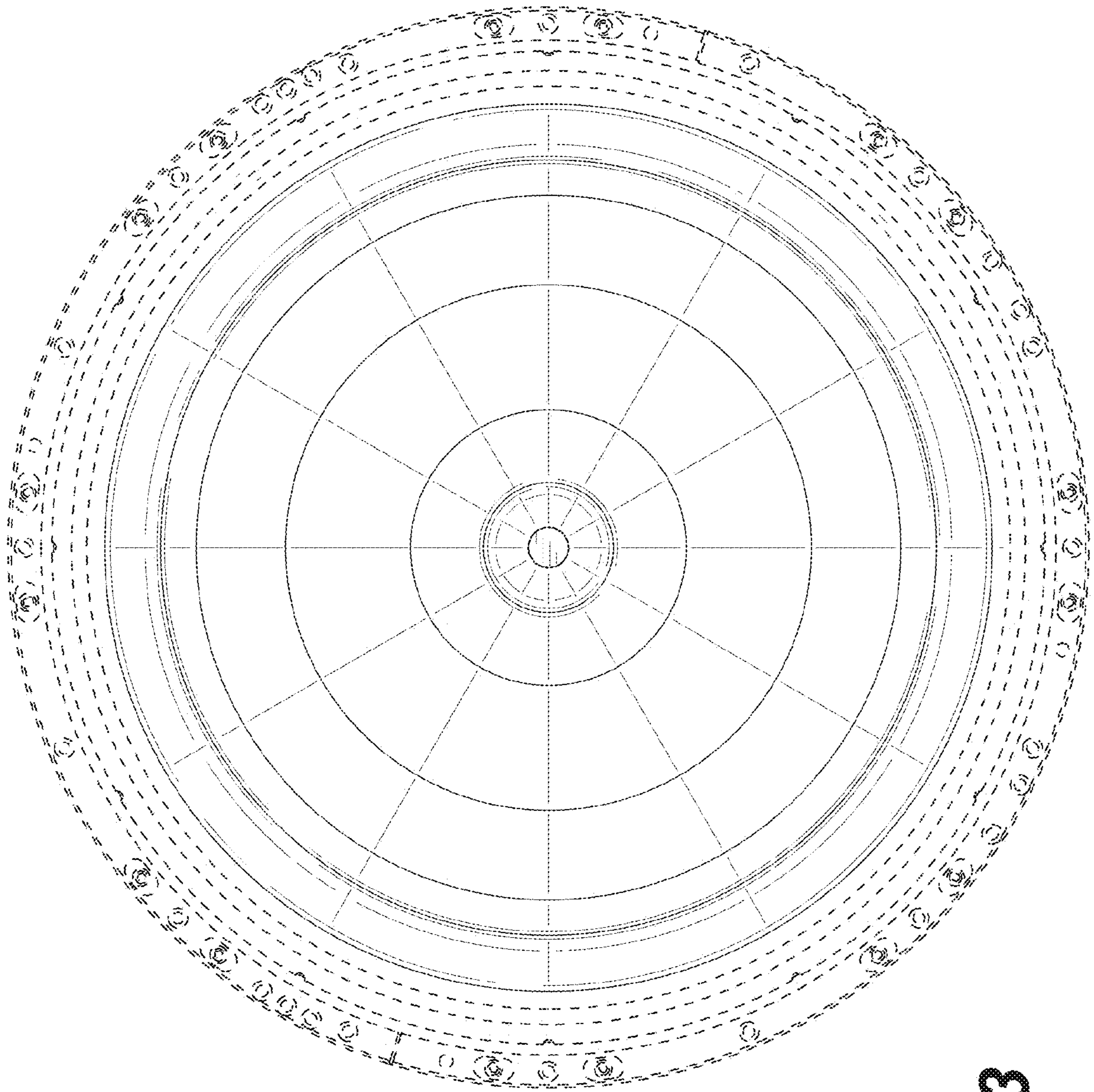


FIG. 3

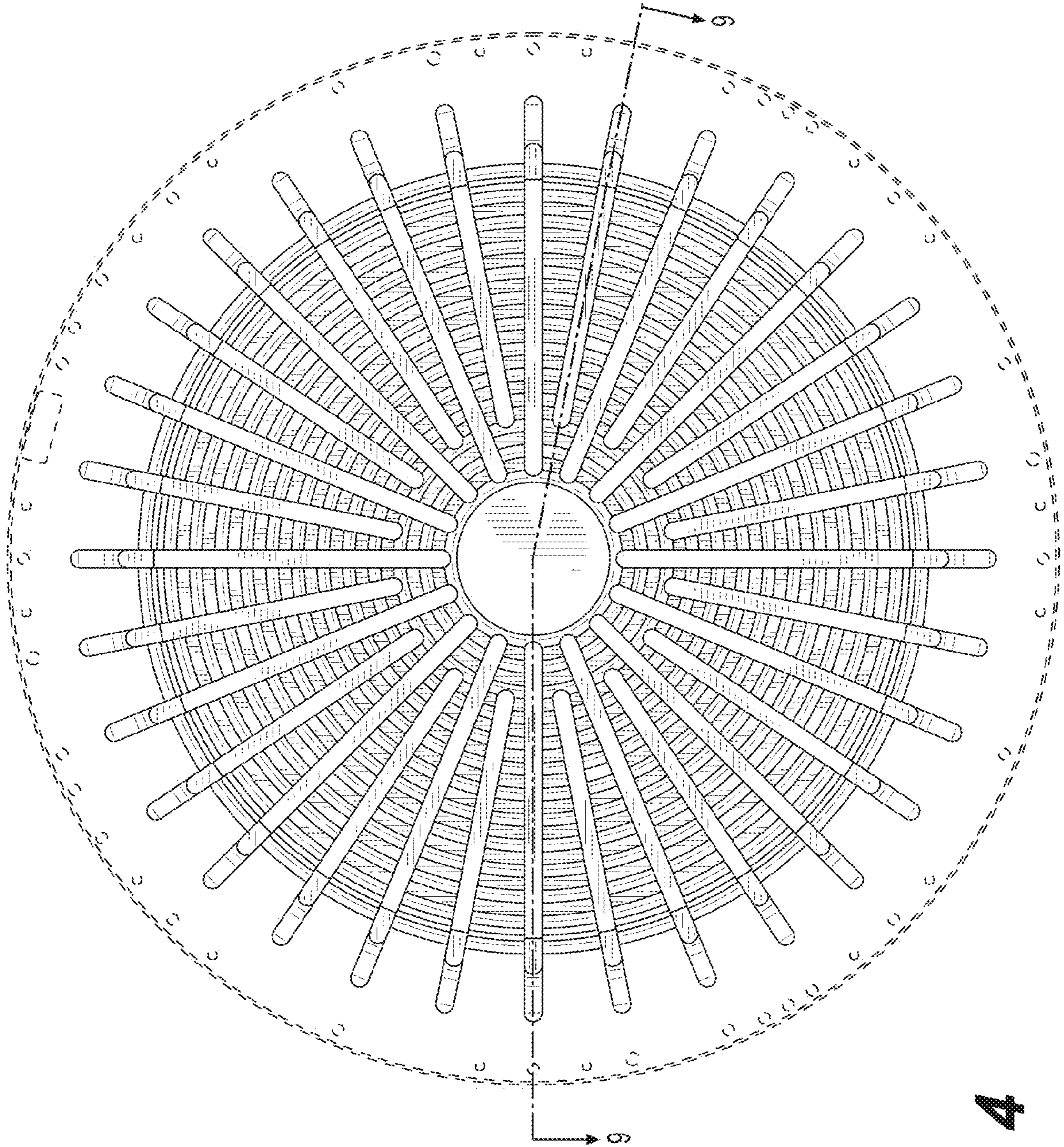


FIG. 4

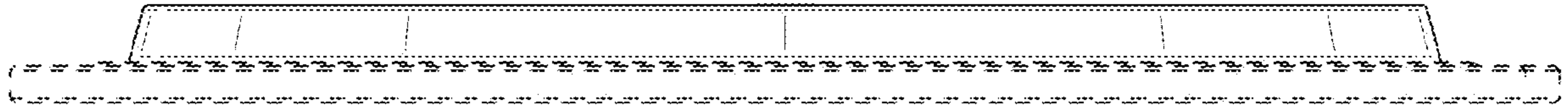


FIG. 5

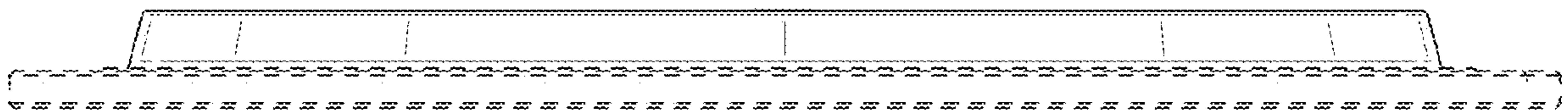


FIG. 6

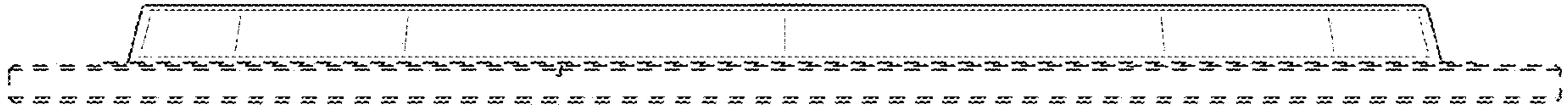


FIG. 7

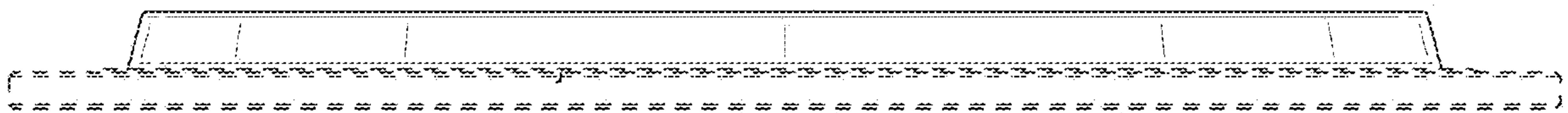


FIG. 8

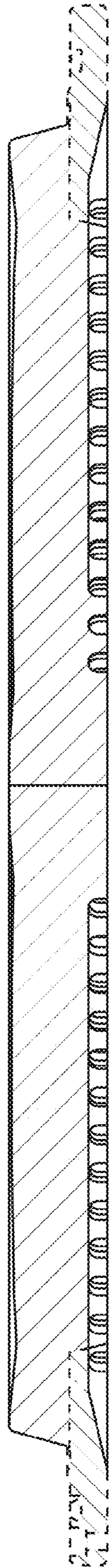


FIG. 9